„Prozess-integrierte zerstörungsfreie Messtechnik für die Dünnschichtabscheidung“

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This tutorial will give an overview of the state-of-art of non-destructive metrology methods for thin film characterization. The main focus will be on optical methods like transmittance, reflectance, and photoluminescence but also electrical methods like eddy current sensing will be introduced. Typical examples for parameters such as thin film thickness, color or sheet resistance that can be deduced from these methods will be explained. After this general introduction, the tutorial will focus on the integration of metrology systems into production environment. Here, stand-alone mapping solutions, automated in-line measurements as well as fully integrated in-situ measurement will be discussed and advantages and disadvantages of each way of integration will be addressed.